

List of reference symbols

- |    |    |                             |
|----|----|-----------------------------|
|    | 1  | semiconductor substrate     |
|    | 2  | first trench                |
| 5  | 3  | oxidized silicon layer      |
|    | 4  | aluminium-oxide layer       |
|    | 5  | horizontal regions          |
|    | 6  | second trench               |
|    | 7  | widened second trench       |
| 10 | 8  | bottle structure            |
|    | 9  | first electrode             |
|    | 10 | dielectric layer            |
|    | 11 | conductive filling          |
|    | 12 | rugged polysilicon layer    |
| 15 | 13 | first silicon nitride layer |
|    | 14 | silicon nitride layer       |
|    | 15 | hardmask                    |
|    | 16 | process window              |